Evaluation of thermal stability in spectrally selective few-layer metallo-dielectric structures for solar thermophotovoltaics

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Highlights

- An extremely high-thermal-stability few-layer structure is proposed.
- A HfO_2 layer on a Mo substrate is more stable than that on a W substrate at 1473 K.
- The degradation of the structure at 1473 K is due to Mo thin-film oxidation.
- The potential stability of few-layer structures for high-temperature applications.